Observation of anisotropic growth and compositional

discontinuity in AlGaN electron-blocking layers on GaN

micro-rods

Woo-Young Jung,  $^{\dagger,\perp}$  Chan-Min Kwak,  $^{\dagger,\perp}$  Jae-Bok Seol,  $^{\sharp,\perp}$  Jin Kuen Park,  $^{\S}$  Chan-Gyung Park  $^{\dagger,\ddagger}$ 

Young Kyu Jeong",\*

<sup>†</sup>Department of Materials Science and Engineering, POSTECH, Pohang 37673, South Korea

<sup>‡</sup>National Institute for Nanomaterials Technology, POSTECH, Pohang 37673, South Korea

§ Department of Chemistry, Hankuk University of Foreign Studies, Yongin 449-791, South Korea

Non-Ferrous Materials Group, KITECH, Gangneung 25440, South Korea

**Corresponding Authors** 

\* Dr. Young K. Jeong, Tel: +82-10-9215-0639, E-mail: immrc80@gmail.com

**Author Contribution** 

<sup>1</sup>These authors contributed to this work equally.

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tomography

	m1-plane	m2-plane	m3-plane	m4-plane	m5-plane	m6-plane	Average	Standard Deviation	Coefficient of Variation
Buffer	165.1	170.0	164.5	154.4	147.6	153.2	159.1	7.89	0.0495
1 <sup>st</sup> Qb	16.8	18.0	17.0	14.4	14.8	14.8	16.0	1.35	0.0844
2 <sup>nd</sup> Qb	15.8	16.2	15.3	13.9	13.9	14.8	15.0	0.86	0.0576
3 <sup>rd</sup> Qb	14.8	16.2	14.4	13.5	13.9	13.9	14.4	0.88	0.0607
4 <sup>th</sup> Qb	31.4	37.7	36.0	36.8	25.2	36.9	34.0	4.45	0.1309
1 <sup>st</sup> Qw	7.2	7.2	7.6	7.2	7.2	7.1	7.3	0.18	0.0243
$2^{nd}$ Qw	6.5	6.3	6.7	6.7	6.7	6.7	6.6	0.18	0.0269
3 <sup>rd</sup> Qw	6.1	6.3	6.3	6.3	6.3	6.3	6.3	0.07	0.0113
4 <sup>th</sup> Qw	6.1	5.8	5.8	5.8	5.8	5.8	5.9	0.10	0.0166
EBL	47.6	51.2	47.2	22.4	9.0	48.1	37.6	15.99	0.4257
p-GaN	202.8	213.1	189.8	214.2	211.4	186.1	202.9	11.24	0.0554
Total	520.2	547.9	510.6	495.6	461.9	493.8	505.0	26.39	5.23

Table. S1. Thickness of each layer on every six m-planes of the micro-rod. Note that EBLs show highest standard deviation (11.99) and coefficient of variation values (0.4257) compared with other layers, indicating their asymmetric growths.

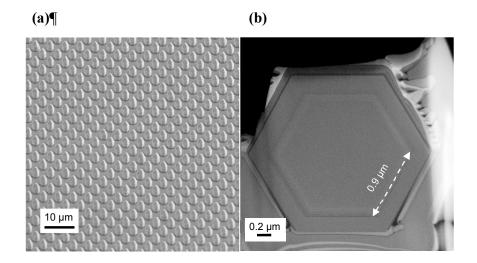


Figure. S1. (a) SEM image of GaN micro-rod LEDs array and (b) cross sectional HAADF-STEM image of the GaN core-shell micro-rod. The length of m-plane ranges in between 0.7 and 1 um.

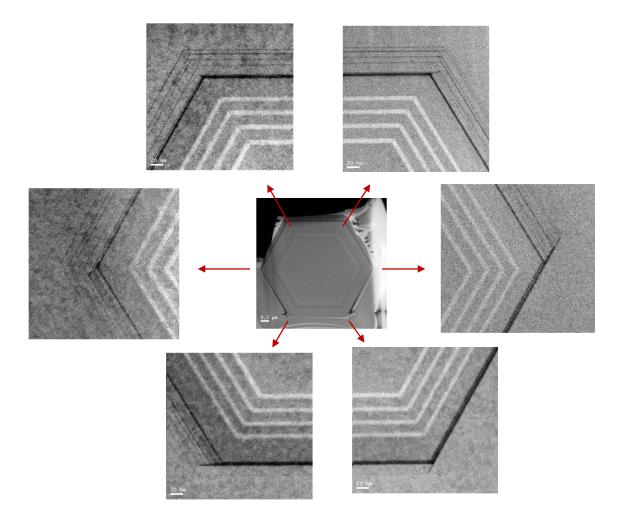


Figure. S2. Cross section HAADF-STEM images acquired at six different m-plane corners of a single micro-rod. The images show the phase-separated AlGaN EBLs that have different thicknesses and lengths on the six m-planes of the GaN micro rod.